## Mn-composition dependence of magnetoresistance ratio of Co<sub>2</sub>MnSi-based giant magneto-resistance devices

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Co-based Heusler alloy thin films have been extensively studied as a promising ferromagnetic electrode material for spintronic devices, including magnetic tunnel junctions (MTJs)<sup>1-4)</sup> and giant magnetoresistance (GMR) devices<sup>5,6)</sup>, and for spin injection into semiconductors.<sup>7)</sup> We have shown that harmful defects in Heusler alloy thin films of Co2MnSi (CMS), Co2(Mn,Fe)Si (CMFS), and Co2MnGe can be suppressed by appropriately controlling the film composition, *i.e.*, Co<sub>Mn</sub> antisites detrimental to the half-metallicity can be suppressed by adding an excess Mn,<sup>1)</sup> and have demonstrated high tunneling magnetoresistance (TMR) ratios of up to 1995% (354%) at 4.2 K (290 K) in CMS/MgO/CMS MTJs having Mn-rich CMS electrodes,<sup>2)</sup> and up to 2611% (429%) at 4.2 K (290 K) in CMFS/MgO/CMFS MTJs having (Mn+Fe)-rich CMFS electrodes.<sup>3)</sup> The purpose of the present study was to clarify the influence of off-stoichiometry for CMS films on the MR ratio of GMR devices.

To do this, we fabricated current-perpendicular-to-plane (CPP)-GMR devices having CMS electrodes with various Mn compositions,  $\alpha$ , and an Ag spacer, and investigated the influence of  $\alpha$  on the magnetoresistance (MR) characteristics.

The fabricated GMR layer structures were as follows: (from the substrate side) MgO buffer (10 nm)/CoFe seed (10)/Ag buffer (100)/CoFe buffer (10)/CMS lower electrode (3)/CoFe (1.1)/Ag spacer (5)/CoFe (1.1)/CMS upper electrode (3)/CoFe (1.1)/IrMn (10)/Ru cap (5) with  $Co_2Mn_{\alpha}Si_{0.82}$  electrodes, grown on MgO(001) substrates. The preparation procedure of CMS electrodes with various values of  $\alpha$  was the same as for the CMS/MgO MTJs.<sup>1-4)</sup> Just after the deposition of CMS upper electrodes, the laver structure was *in-situ* annealed at 550 °C. We fabricated GMR devices with the nominal junction sizes ranging from  $70 \times 120 \text{ nm}^2$  to  $400 \times 640 \text{ nm}^2$  by using EB lithography and Ar ion milling. The MR characteristics were measured using a dc four-probe method at room temperature.

Figure 1 shows a typical MR curve for a GMR device having Co<sub>2</sub>Mn<sub>1.45</sub>Si<sub>0.82</sub> electrodes. It showed clear MR characteristics with a MR ratio of approximately 17%. The values of  $R_{\rm P}$ ·A and  $\Delta R$ ·A were 52 m $\Omega$ ·µm<sup>2</sup> and 8.4 m $\Omega$ ·µm<sup>2</sup>, respectively, where  $\Delta R = R_{AP} - R_P, R_{P(AP)}$ is the junction resistance for parallel (antiparallel) configuration, and A is the nominal junction size. Figure 2 shows MR ratios as a function of Mn composition,  $\alpha$ . The MR ratio increased with increasing  $\alpha$  from 9% for Mn-deficient  $\alpha = 0.62$  to 17% for Mn-rich  $\alpha = 1.45$ . This result suggests a continuous increase in the spin polarization with increasing  $\alpha$  from a Mn-deficient to a Mn-rich composition. Thus, it is demonstrated that enhancing the half-metallicity of CMS by appropriate control of the film composition toward a Mn-rich one is also highly effective in CMS-based GMR devices as in the MTJs.

## References

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Fig. 1. A typical MR curve at 290 K for a CMS/CoFe (1.1 nm)/Ag/CoFe (1.1 nm)/CMS GMR device with Mn-rich α = 1.45 CMS electrodes. The nominal junction size was  $70 \times 120 \text{ nm}^2$ .



Fig. 2. MR ratios at 290K for CMS/CoFe (1.1 nm)/Ag/CoFe (1.1 nm)/CMS GMR devices as a function of the film composition  $\alpha$  $Co_2Mn_{\alpha}Si_{0.82}$  electrodes.